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 APPLICATION NO.
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 Jae Hong Kim
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MARSHALL, GERSTEIN & BORUN LLP 6300 SEARS TOWER 233 S. WACKER DRIVE CHICAGO, IL 60606 EXAMINER
SARKAR, ASOK K

ART UNIT

PAPER NUMBER

2829

DATE MAILED: 08/27/2003

Please find below and/or attached an Office communication concerning this application or proceeding.

		T		M-
		Application No.	Applicant(s)	
• •		10/038,375	KIM ET AL.	
	Office Action Summary	Examiner	Art Unit	
		Asok K. Sarkar	2829	
Period fo	• •	•	·	
THE I - Exter after - If the - If NO - Failur - Any r	ORTENED STATUTORY PERIOD FOR REPL MAILING DATE OF THIS COMMUNICATION. Issions of time may be available under the provisions of 37 CFR 1. SIX (6) MONTHS from the mailing date of this communication. period for reply specified above is less than thirty (30) days, a reperiod for reply is specified above, the maximum statutory period re to reply with the set or extended period for reply will, by statutely received by the Office later than three months after the mailing dispatch term adjustment. See 37 CFR 1.704(b).	136(a). In no event, however, may a reply be oly within the statutory minimum of thirty (30) of will apply and will expire SIX (6) MONTHS from e, cause the application to become ABANDO	timely filed lays will be considered timely. om the mailing date of this communication. NED (35 U.S.C. § 133).	
1)🛛	Responsive to communication(s) filed on 15	<u>May 2003</u> .		
2a) <u></u> □	This action is FINAL . 2b)⊠ T	his action is non-final.		
3)□ Dispositi	Since this application is in condition for allow closed in accordance with the practice under on of Claims			\$
4) 🖾	Claim(s) 1.3.5-13 and 24 is/are pending in th	e application.		
	4a) Of the above claim(s) is/are withdra	awn from consideration.		
5)	Claim(s) is/are allowed.			
6)⊠	Claim(s) <u>1,3,5-13 and 24</u> is/are rejected.			
7)	Claim(s) is/are objected to.			
8) 🗌	Claim(s) are subject to restriction and/	or election requirement.		
Applicati	on Papers			
9) 🗌 -	The specification is objected to by the Examin	er.		
10)🛛	The drawing(s) filed on <u>04 January 2002</u> is/are	e: a)⊠ accepted or b)□ objected t	o by the Examiner.	
	Applicant may not request that any objection to the	ne drawing(s) be held in abeyance.	See 37 CFR 1.85(a).	
11) 🔲 🗀	The proposed drawing correction filed on	_ is: a)□ approved b)□ disapp	proved by the Examiner.	
	If approved, corrected drawings are required in re	eply to this Office action.		
12) 🗌 -	Γhe oath or declaration is objected to by the Ε	xaminer.		
Priority u	nder 35 U.S.C. §§ 119 and 120			
13)⊠	Acknowledgment is made of a claim for foreig	n priority under 35 U.S.C. § 119	(a)-(d) or (f).	
a)[☑ All b)☐ Some * c)☐ None of:			
	1. Certified copies of the priority document	ts have been received.		
	2. Certified copies of the priority documen	ts have been received in Applic	ation No	
* S	3. Copies of the certified copies of the prior application from the International Bree the attached detailed Office action for a lis	ureau (PCT Rule 17.2(a)).	•	
14) 🗌 A	cknowledgment is made of a claim for domes	tic priority under 35 U.S.C. § 11	9(e) (to a provisional applicatio	on).
	The translation of the foreign language pracknowledgment is made of a claim for domes	* *		
Attachment	-			
2) Notic	e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (PTO-948) nation Disclosure Statement(s) (PTO-1449) Paper No(s)	5) Notice of Inform	ary (PTO-413) Paper No(s) al Patent Application (PTO-152)	
J.S. Patent and Ti PTOL-326 (R		Action Summary	Part of Paper No. 12	2



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DETAILED ACTION

Continued Examination Under J7 CFR 1.114

1. A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on July 14, 2003 has been entered.

Response to Arguments

2. Applicant's arguments with respect to claims 1, 3, 5 – 13 and 24 have been considered but are moot in view of the new ground(s) of rejection.

Claim Objections

- 3. Claims 3, 5 and 8 10 are objected to because of the following informalities:

 The word "about" in describing the range should be deleted to make the claim language clear. Appropriate correction is required.
- 4. Claim 5 is objected to because of the following informalities: Claim 5 should depend on 1 instead of cancelled claim 4. Appropriate correction is required.

Claim Rejections - 35 USC § 102

5. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the



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applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

6. Claims 1, 3, 5, 6, 8 – 13 and 24 are rejected under 35 U.S.C. 102(e) as being anticipated by Sinha, US 6,551,935.

Regarding claim 1, Sinha teaches a polishing slurry comprising:

- an oxidant (oxidizer) consisting essentially of ceric ammonium nitrate (column 3, line 12 and column 5, line 39);
- an abrasive containing essentially of inorganic particles in column 5, lines 13
 and column 6, lines 1 5; and
- an acid selected from the group of H₃PO₄ and H₂SO₄ and mixtures thereof in column 6, lines 19 20. Sinha teaches HNO₃ (also as an oxidizer) in column 11, line 7.

Regarding claim 3, Sinha teaches ceric ammonium nitrate agent is present within the range of 1 – 10 wt% in column 5, lines 41 - 42.

Regarding claim 5, Sinha teaches HNO_3 is present from 1 – 10 wt% of the slurry in claim 35 in column 11, lines 10 - 11.

Reagrding claim 6, Sinha teaches inorganic particles of the abrasive are selected from a group consisting of CeO_2 particles and Al_2O_3 particles and mixtures thereof in column 6, lines 1 – 5.

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Reagrding claim 8, Sinha teaches abrasive particles amount of 1 - 5 wt% in column 6, lines 1 - 5.

Reagrding claim 9, Sinha teaches pH of the slurry in the range of 3 - 7 in column 6, lines 6 – 7.

Regarding claim 10, Sinha teaches pH of the slurry to be 3 in column 6, lines 6 – 7.

Regarding claim 11, Sinha teaches slurry comprising a buffer solution (pH control agents) in column 6, line 15.

Regarding claim 12, Sinha teaches buffer solution comprising a mixture of organic acid and organic acid salt column 6, lines 15 – 21. Buffer solutions are inherently equimolar mixture of weak acids and their salts.

Regarding claim 13, Sinha teaches buffer solution comprising a mixture of acetic acid and ammonium acetic acid salt column 6, lines 15 – 21.

Regarding claim 24, Sinha teaches a polishing slurry comprising:

- a single oxidant (oxidizer) consisting essentially of ceric ammonium nitrate
 (column 3, line 12 and column 5, line 39); and
- an abrasive containing essentially of inorganic particles in column 5, lines 13
 and column 6, lines 1 5.
- 7. Claims 1, 3 and 5 11 are rejected under 35 U.S.C. 102(e) as being anticipated by Liu, US 6,491,837.

Regarding claim 1, Liu teaches a polishing slurry comprising:



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- an oxidant (co-oxidizer) consisting essentially of ceric ammonium nitrate (column
 4, line 27 and line 38);
- an abrasive containing essentially of inorganic particles in column 4, lines 1 5;
 and
- an acid selected from the group of HNO₃, H₂SO₄, HCI and H₃PO₄ and mixtures
 thereof in column 4, lines 19 20. Liu teaches HNO₃ (also as an oxidizer) in
 column 4, line 15 thereby making the oxidizer part of the acid and the co-oxidizer
 the only oxidant.

Regarding claim 3, Liu teaches ceric ammonium nitrate agent is present within the range of 1-4 wt% in column 4, lines 40-41.

Regarding claim 5, Liu teaches HNO_3 is present from 1 – 7.5 wt% of the slurry in column 4, lines 22 - 23.

Regarding claim 6, Liu teaches inorganic particles of the abrasive are selected from a group consisting of CeO2 particles and Al_2O_3 particles and ZrO_2 particles in column 4, lines 2-4.

Regarding claim 7, Liu teaches size of the abrasive particles is below 1 micron in column 4, lines 1-5.

Reagrding claim 8, Liu teaches abrasive particles amount of 1-5 wt% in column 3, line 66.

Reagrding claim 9, Liu teaches pH of the slurry in the range of 1 - 5 in column 5, line 1.

Regarding claim 10, Liu teaches pH of the slurry to be 1 – 3 in column 5, line 1.



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Regarding claim 11, Liu teaches slurry comprising a buffer solution in column 4, line 63.

Claim Rejections - 35 USC § 103

- 8. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 9. Claim 7 is rejected under 35 U.S.C. 103(a) as being unpatentable over Sinha, US 6,551,935 in view of Yano, US 6,375,545.

Sinha fails to teach the size of the abrasive particles.

Yano teaches a CMP slurry where he teaches size of the abrasive particles is below 1 micron in column 11, lines 50 – 52 so that the inorganic particles do not nick the wafer during polishing in column 12, lines 31 - 41.

Therefore, it would have been obvious to one with ordinary skill in the art at the time of the invention to modify Sinha's slurry by controlling the size of the abrasive particles to below 1 micron so that the abrasives do not nick the wafer as taught by Yano in column 12, lines 31 - 41.

Double Patenting

10. A rejection based on double patenting of the "same invention" type finds its support in the language of 35 U.S.C. 101 which states that "whoever invents or discovers any new and useful process ... may obtain <u>a</u> patent therefor ..." (Emphasis added). Thus, the term "same invention," in this context, means an invention drawn to

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identical subject matter. See *Miller v. Eagle Mfg. Co.*, 151 U.S. 186 (1894); *In re Ockert*, 245 F.2d 467, 114 USPQ 330 (CCPA 1957); and *In re Vogel*, 422 F.2d 438, 164 USPQ 619 (CCPA 1970).

A statutory type (35 U.S.C. 101) double patenting rejection can be overcome by canceling or amending the conflicting claims so they are no longer coextensive in scope. The filing of a terminal disclaimer <u>cannot</u> overcome a double patenting rejection based upon 35 U.S.C. 101.

11. Claims 1, 3, 5 – 13 and 24 are provisionally rejected under 35 U.S.C. 101 as claiming the same invention as that of claims 1, 3, 5 – 13 and 29 of copending Application No. 10/096,266. This is a <u>provisional</u> double patenting rejection since the conflicting claims have not in fact been patented.

Conclusion

12. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Asok K. Sarkar whose telephone number is 703 308 2521. The examiner can normally be reached on Monday - Friday (8 AM- 5 PM).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Kammie Cuneo can be reached on 703 308 1233. The fax phone numbers for the organization where this application or proceeding is assigned are 703 308 7722 for regular communications and 703 308 7722 for After Final communications.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703 308 4918.

Asoli Univer Souther Asok K. Sarkar August 18, 2003